

In the Claims:

Please cancel claim 1-7 without prejudice.

Original claims 8-14 are pending as follows:

Claims 1-7 (canceled)

8. (original) A method for producing the redundantly constrained laminar structures as weak-link mechanisms by lithographic techniques comprising the steps of:
repeatedly chemically etching a designed pattern with a mask to produce a plurality of individual substantially identical units; and
stacking the units together to form the laminar structure.

9. (original) A method for producing the redundantly constrained laminar structures as weak-link mechanisms as recited in claim 8 further includes the steps of securing the stacked units together with fasteners received in predefined locating-holes in said units; and applying an adhesive to the sides of the laminar structure to provide the mechanism equivalent to a single piece mechanism.

10. (original) A method for producing the redundantly constrained laminar structures as weak-link mechanisms as recited in claim 8 wherein each of said plurality of individual substantially identical units is formed of a thin material.

11. (original) A method for producing the redundantly constrained laminar structures as weak-link mechanisms as recited in claim 8 wherein each of said plurality of individual substantially identical units is formed of a thin metal material.

12. (original) A method for producing the redundantly constrained laminar structures as weak-link mechanisms as recited in claim 8 wherein the step of repeatedly

chemically etching a designed pattern with a mask to produce a plurality of individual substantially identical units includes the step of repeatedly chemically etching a designed pattern having multiple weak-link connections with a mask to produce a plurality of individual substantially identical units

13. (original) A method for producing the redundantly constrained laminar structures as weak-link mechanisms as recited in claim 8 wherein the step of repeatedly chemically etching a designed pattern with a mask to produce a plurality of individual substantially identical units includes the step of repeatedly chemically etching a designed pattern with a mask to produce a set number of individual substantially identical units.

14. (original) A method for producing the redundantly constrained laminar structures as weak-link mechanisms as recited in claim 13 wherein said set number of individual substantially identical units is selected for providing a predefined stiffness for the laminar structure.